Form PTO 1449		U.S. DEPARTMENT OF COMMERCE		ATTY DOCKET NO.		SERIAL NO.			
(Modified)		PATENT AND TRAD	EMARK OFFICE	246036US2		New Application			
			APPLICANT						
LIST OF REFERENCES CITED BY APPLICANT .				Masato HIRAMATSU, et al.					
				FILING DATE		GROUP			
				Herewith					
U.S. PATENT DOCUMENTS									
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS			
	ĀĀ							-	
	AB								
	AC								
	AD								
	AE								
	AF								
	AG								
	AH								
	Al								
	AJ								
FOREIGN PATENT DOCUMENTS									
		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION YES · NO				
DHA	AK	2002-289865	10/04/2002	JAPAN (with English Abstract)	-			×	
	AL								
	AM		<u> </u>						
	AN								
	AO								
OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)									
Shinya TSUDA, et al., "PREPARATION AND PROPERTIES OF HIGH-QUALITY a-Si FILMS WITH A SUPER CHAMBER (SEPARATED ULTRA-HIGH VACUUM REACTION CHAMBER)", Japanese Journal of Applied Physics, Vol. 26, No. 1, January 1987, pgs. 33-38								PER CHAMBER /ol. 26, No. 1,	
	AQ	C. C. TSAI, et al., "CLEAN" a-Si:H PREPARED IN A UHV SYSTEM", Journal of Non-Crystalline Solids, Vol. 66, 1984, pgs. 45-50							
	AR	Masato HIRAMATSU, et al., "AN ADVANCED PECVD SYSTEM FOR MASS-PRODUCING HIGH-PURITY SITHIN FILMS", IDW '02 Proceedings of the Ninth International Display Workshops, December 4-6, 2002, 2 pgs							
	AS	Masato HIRAMATSU, et al., "MECHANISM OF OXYGEN CONTAMINATION IN PECVD A-SI:H FILMS", Electrochemical Society Proceedings Volume 2003-08, pgs. 701-707							
	AT	Toshihiro KAMEI, et al., "DEPOSITION OF ULTRAPURE HYDROGENATED AMORPHOUS SILICON", J. Vac. Sci. Technol. A, Vol. 17, No. 1, Jan/Feb 1999, pgs. 113-120							
	AU	U. KROLL, et al., "ORIGINS OF ATMOSPHERIC CONTAMINATION IN AMORPHOUS SILICON PREPARED BY VERY HIGH FREQUENCY (70 MHz) GLOW DISCHARGE", J. Vac. Sci. Technol. A, Vol. 13, No. 6, Nov/Dec 1995, pgs. 2742-2746							
	AV	A. A. HOWLING, et al., "FREQUENCY EFFECTS IN SILANE PLASMAS FOR PLASMA ENHANCED CHEMICAL VAPOR DEPOSITION", J. Vac. Sci. Technol. A, Vol. 10, No. 4, Jul/Aug 1992, pgs. 1080-1085						sheet(s) attached	
Examiner Kang, Donghee						Date Considered 04-06-05			
*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in									
conformance and not considered, include copy of this form with next communication to applicant.									